

1 James R. Patterson, SBN 211102  
jim@pattersonlawgroup.com  
2 Jennifer M. French, SBN 265422  
jenn@pattersonlawgroup.com  
3 **PATTERSON LAW GROUP, APC**  
4 1350 Columbia Street, Unit 603  
San Diego, California 92101  
5 Telephone: (619) 756-6990  
Facsimile: (619) 756-6991

6 Alan Block (SBN 143783)  
7 ablock@mckoolsmith.com  
**MCKOOL SMITH, P.C.**  
8 300 South Grand Avenue, Suite 2900  
Los Angeles, California 90071  
9 Telephone: (213) 694-1200  
10 Facsimile: (213) 694-1234

11 Christopher R. Clayton\* (MO SBN 69692)  
**DEVLIN LAW FIRM LLC**  
12 1526 Gilpin Avenue  
Wilmington, Delaware 19806  
13 Telephone: (302) 449-9010  
Facsimile: (302) 353-4251  
14 \* *Admitted pro hac vice*

15 Attorneys for Plaintiff

16  
17 **IN THE UNITED STATES DISTRICT COURT**  
18 **FOR THE SOUTHERN DISTRICT OF CALIFORNIA**  
19

20 BELL SEMICONDUCTOR, LLC  
21 Plaintiff,  
22 v.  
23 NXP USA, INC.  
24 Defendant.

**Case No. 3:22-cv-00594-H-KSC**  
**SECOND AMENDED**  
**COMPLAINT**  
  
**JURY TRIAL DEMANDED**

1 Plaintiff Bell Semiconductor, LLC (“Bell Semic” or “Plaintiff”) brings this  
2 Complaint against Defendant NXP USA, Inc. (“NXP”) for infringement of U.S. Patent  
3 No. 7,007,259 (“the ’259 patent”) and U.S. Patent No. 6,436,807 (“the ’807 patent”).  
4 Plaintiff, on personal knowledge of its own acts, and on information and belief as to all  
5 others based on investigation, alleges as follows:

6 **SUMMARY OF THE ACTION**

7 1. This is a patent infringement suit relating to NXP’s unauthorized and  
8 unlicensed use of the ’259 and ’807 patents. The circuit design methodologies claimed  
9 in the ’259 and ’807 patents are used by NXP in the production of one or more of its  
10 semiconductor chips, including at least the NXP LS1043A Quad-Core Networking  
11 Processor devices (“NXP Accused Product”).

12 2. Semiconductor devices include different kinds of materials to function as  
13 intended. For example, these devices typically include both metal (*i.e.*, conductor) and  
14 insulator materials, which are deposited or otherwise processed sequentially in layers  
15 to form the final device. These layers—and the interconnects and components formed  
16 within them—have gotten much smaller over time, increasing the performance of these  
17 devices dramatically. As a result, it has become even more important to keep the layers  
18 planar as the device is being built because defects and warpage can cause fabrication  
19 issues and malfunctioning of the device. Manufacturers use a process called Chemical  
20 Mechanical Planarization/Polishing (“CMP”) to smooth out the surface of the device to  
21 prepare the device for further processing, such as deposition of another layer. This  
22 allows subsequent layers to be built and connected more easily with fewer opportunities  
23 for short circuits or other errors that render the device defective. CMP functions best  
24 when there is a certain density and variance of the same material on the surface of the  
25 chip. This is because different materials will be “polished” away at different rates,  
26 leading to erosion or dishing on the surface. To reduce this problem “dummy” material,  
27 also known as “dummy fill,” is typically inserted into low-density regions of the device

1 to increase the overall uniformity of the structures on the surface of the layer and reduce  
2 the density variability across the surface of the device. However, dummy fill can  
3 increase capacitance if it is placed too close to signal wires, which slows the  
4 transmission speed of signals and degrades the overall performance of the device.

5 3. Prior to development of the methodology described in the '807 patent, the  
6 placement of dummy fill in the open areas of the interconnect layer was performed  
7 based upon a predetermined set density. However, use of predetermined set densities  
8 was not ideal because it often resulted in unnecessary placement of dummy fill and  
9 increased capacitance. For example, if the density of an active interconnect feature was  
10 high in relation to an adjacent open area, then it would not be necessary to place dummy  
11 fill in the corresponding open area at the predetermined density.

12 4. Recognizing these drawbacks, as well as the importance of having a flat or  
13 planarized surface on the devices, Donald Cwynar, Sudhanshu Misra, Dennis Ouma,  
14 Vivek Saxena, and John Sharpe (“the '807 Inventors”), the inventors of the '807 patent,  
15 set out to develop a design process that would achieve uniform density throughout the  
16 interconnect layer.

17 5. The '807 Inventors ultimately conceived of a method for making the layout  
18 for an interconnect layout that allows for uniform density throughout the layer and  
19 facilitates planarization during manufacturing of the device. The claimed invention  
20 begins by determining an active interconnect feature density for each of a plurality of  
21 layout regions of the interconnect layout. Dummy fill is then added to each layout  
22 region in order to obtain a desired density of active interconnect features and dummy  
23 fill features in order to facilitate uniformity of planarization. In order to add dummy fill  
24 in this manner, one must define a minimum dummy fill feature lateral dimension based  
25 upon a dielectric layer deposition bias for a dielectric layer to be deposited over the  
26 interconnect layer.

1           6. The inventions disclosed in the '807 patent provide many advantages over the  
2 prior art. In particular, having a uniform density for each layout region facilitates  
3 uniformity of planarization during manufacturing of the semiconductor device. *See Ex.*  
4 *D* at 3:3–5, 5:9–12. Furthermore, adding dummy fill features to obtain a desired density  
5 of active interconnect features and dummy fill features also helps ensure that dummy  
6 fill features are not unnecessarily added. *Id.* at 2:63–67, 5:19–22. Avoiding unnecessary  
7 dummy fill features is desirable because it decreases the parasitic capacitance of the  
8 interconnect layer. *Id.* at 2:67–3:2, 5:22–24. The invention claimed in the '807 patent  
9 also provides for the selective positioning of dummy fill features, which minimizes  
10 parasitic capacitance. *Id.* at 5:28–33. These significant advantages are achieved through  
11 the use of the patented inventions and thus the '807 patent presents significant  
12 commercial value for companies like NXP.

13           7. The development of the design methodology claimed in the '259 patent  
14 represented another important advancement related to the design of semiconductor  
15 devices. Prior to development of the methodology described in the '259 patent, the  
16 most widely implemented technology for insertion of dummy metal into a circuit design  
17 required hardcoding a large “stay-away” distance between the dummy metal and clock  
18 nets, which led to less space available for dummy metal insertion. This methodology  
19 often made it impossible to insert enough dummy metal to meet the required minimum  
20 density. The traditional dummy fill tools would often complete their run without  
21 reaching the minimum density, thus requiring at least a second run of the tool for the  
22 problem areas. In each problem area, the “stay-away” distance was reduced manually.  
23 And if there were more than one problem area, the manufacturer would have to make  
24 multiple runs of the tool, as it would have to address one problem area at a time. This  
25 was an involved, iterative process that had the potential to negatively impact the  
26 fabrication schedule and potentially the yield of the run, causing costs to go up.

1           8. Vikram Shrowty and Santhanakrishnan Raman (“the ’259 Inventors”), the  
2 inventors of the ’259 patent, understood the drawbacks of this “stay-away” design  
3 process and set out to develop a more efficient method for inserting dummy metal into  
4 a circuit design. The ’259 Inventors ultimately conceived of a dummy fill procedure  
5 that minimizes the negative timing impact of dummy metal on clock nets, while still  
6 achieving minimum density in a single run. The claimed invention begins by identifying  
7 free spaces on each layer of the circuit design suitable for dummy metal insertion as  
8 dummy regions. The dummy regions are then prioritized such that the dummy regions  
9 located adjacent to clock nets are filled with dummy metal last, thereby minimizing any  
10 timing impact on the clock nets.

11           9. The inventions disclosed in the ’259 patent provide many advantages over the  
12 prior art. In particular, they provide a simple and efficient method for dummy metal  
13 insertion that minimizes the timing impact to clock nets and at the same time guarantees  
14 reaching minimum density in a single pass. *See Ex. A at 6:11–15.* As mentioned above,  
15 the patented invention results in the dummy regions being prioritized such that the  
16 dummy regions located adjacent to clock nets are filled with dummy metal last, thereby  
17 minimizing the timing impact on the clock nets. *See Ex. A at 2:29–47.* Additionally,  
18 some embodiments of the patented invention further prioritize the dummy regions such  
19 that the dummy regions adjacent to wider clock nets are filled with dummy metal after  
20 dummy regions that are located adjacent to narrower clock nets. *See Ex. A at 2:35–39.*  
21 These significant advantages are achieved through the use of the patented inventions  
22 and thus the ’259 patent presents significant commercial value for companies like NXP.

23           10. Bell Semic brings this action to put a stop to NXP’s unauthorized and  
24 unlicensed use of the inventions claimed in the ’259 and ’807 patents.

1 **THE PARTIES**

2 11. Plaintiff Bell Semic is a limited liability company organized under the  
3 laws of the State of Delaware with a place of business at One West Broad Street, Suite  
4 901, Bethlehem, PA 18018.

5 12. Bell Semic stems from a long pedigree that began at Bell Labs. Bell Labs  
6 sprung out of the Bell System as a research and development laboratory, and eventually  
7 became known as one of America’s greatest technology incubators. Bell Labs  
8 employees invented the transistor in 1947 in Murray Hill, New Jersey. It was widely  
9 considered one of the most important technological breakthroughs of the time, earning  
10 the inventors the Nobel Prize in Physics. Bell Labs made the first commercial  
11 transistors at a plant in Allentown, Pennsylvania. For decades, Bell Labs licensed its  
12 transistor patents to companies throughout the world, creating a technological boom  
13 that led to the use of transistors in the semiconductor devices prevalent in most  
14 electronic devices today.

15 13. Bell Semic, a successor to Bell Labs’ pioneering efforts, owns over 1,900  
16 worldwide patents and applications, approximately 1,500 of which are active United  
17 States patents. This patent portfolio of semiconductor-related inventions was  
18 developed over many years by some of the world’s leading semiconductor companies,  
19 including Bell Labs, Lucent Technologies, Agere Systems, and LSI Logic and LSI  
20 Corporation (“LSI”). This portfolio reflects technology that underlies many important  
21 innovations in the development of semiconductors and integrated circuits for high-tech  
22 products, including smartphones, computers, wearables, digital signal processors, IoT  
23 devices, automobiles, broadband carrier access, switches, network processors, and  
24 wireless connectors.

25 14. The principals of Bell Semic all worked at Bell Labs’ Allentown facility,  
26 and have continued the rich tradition of innovating, licensing, and helping the industry  
27 at large since those early days at Bell Labs. For example, Bell Semic’s CTO was a LSI  
28

1 Fellow and Broadcom Fellow. He is known throughout the world as an innovator with  
2 more than 300 patents to his name, and he has a sterling reputation for helping  
3 semiconductor fabs improve their efficiency. Bell Semic's CEO took a brief hiatus from  
4 the semiconductor world to work with Nortel Networks in the telecom industry during  
5 its bankruptcy. His efforts saved the pensions of tens of thousands of Nortel retirees  
6 and employees. In addition, several Bell Semic executives previously served as  
7 engineers at many of these companies and were personally involved in creating the  
8 ideas claimed throughout Bell Semic's extensive patent portfolio.

9 15. On information and belief, NXP has its principal place of business and  
10 headquarters at 6501 William Cannon Drive West, Austin, TX 78735.

11 16. On information and belief, NXP develops, designs, and/or manufactures  
12 products in the United States, including in this District, according to the '259 and '807  
13 patented processes/methodologies; and/or uses the '259 and '807 patented  
14 processes/methodologies in the United States, including in this District, to make  
15 products; and/or distributes, markets, sells, or offers to sell in the United States and/or  
16 imports products into the United States, including in this District, that were  
17 manufactured or otherwise produced using the patented process. Additionally, NXP  
18 introduces those products into the stream of commerce knowing that they will be sold  
19 and/or used in this District and elsewhere in the United States.

20 **JURISDICTION AND VENUE**

21 17. This is an action for patent infringement arising under the Patent Laws of  
22 the United States, Title 35 of the United States Code. Accordingly, this Court has  
23 subject matter jurisdiction under 28 U.S.C. §§ 1331 and 1338(a).

24 18. This Court has personal jurisdiction over NXP under the laws of the State  
25 of California, due at least to its substantial business in California and in this District.  
26 NXP has purposefully and voluntarily availed itself of the privileges of conducting  
27 business in the United States, in the State of California, and in this District by  
28



1 continuously and systematically placing goods into the stream of commerce through an  
2 established distribution channel with the expectation that they will be purchased by  
3 consumers in this District. In the State of California and in this District, NXP, directly:  
4 (i) performs at least a portion of the infringements alleged herein; (ii) develops, designs,  
5 and/or manufactures products according to the '259 and '807 patented  
6 processes/methodologies; (iii) distributes, markets, sells, or offers to sell products  
7 formed according to the '259 and '807 patented processes/methodologies; and/or (iv)  
8 imports products formed according to the '259 and '807 patented  
9 processes/methodologies.

10 19. On information and belief, venue is proper in this Court pursuant to 28  
11 U.S.C. §§ 1391 and 1400 because NXP has committed, and continues to commit, acts  
12 of infringement in this District and has a regular and established place of business in  
13 this District. For example, NXP maintains a regular and established place of business  
14 in the District at Innovation Drive, Suite 150, San Diego, CA 92128. On information  
15 and belief, NXP current employs more than 75 engineers in the San Diego area. *See*  
16 Search Results for Current NXP Employees, LinkedIn (available at  
17 [https://www.linkedin.com/search/results/people/?currentCompany=%5B%221088%22%5D&geoUrn=%5B%22103918656%22%2C%2290010472%22%5D&keywords=engineer&origin=FACETED\\_SEARCH&sid=or8](https://www.linkedin.com/search/results/people/?currentCompany=%5B%221088%22%5D&geoUrn=%5B%22103918656%22%2C%2290010472%22%5D&keywords=engineer&origin=FACETED_SEARCH&sid=or8)) (last visited January 6, 2022).

20 20. Currently, on information and belief, NXP is advertising jobs in the San  
21 Diego area. These positions include those that relate to the '259 and '807 patented  
22 technologies, such as a position for an MCU/MPU Engineering Quality and  
23 Infrastructure PM. *See NXP Job Listings*, NXP  
24 ([https://nxp.wd3.myworkdayjobs.com/careers?Location\\_Country=bc33aa3152ec42d4995f4791a106ed09&locations=98d67abaaa8a100fa6344859d7d49369](https://nxp.wd3.myworkdayjobs.com/careers?Location_Country=bc33aa3152ec42d4995f4791a106ed09&locations=98d67abaaa8a100fa6344859d7d49369)) (last visited  
25 January 6, 2022).



1 21. Venue is also convenient in this District. This is at least true because of  
2 this District’s close ties to this case—including the technology, relevant witnesses, and  
3 sources of proof noted above—and its ability to quickly and efficiently move this case  
4 to resolution.

5 22. On information and belief, Bell Semic’s cause of action arises directly  
6 from NXP’s circuit design work and other activities in this District. Moreover, on  
7 information and belief, NXP has derived substantial revenues from its infringing acts  
8 occurring within the State of California and within this District.

9 **U.S. PATENT NO. 7,007,259**

10 23. Bell Semiconductor is the owner by assignment of the ’259 patent. The  
11 ’259 patent is titled “Method for Providing Clock-Net Aware Dummy Metal Using  
12 Dummy Regions.”

13 24. A true and correct copy of the ’259 patent is attached as Exhibit A.

14 25. The inventors of the ’259 patent are Vikram Shrowty and  
15 Santhanakrishnan Raman.

16 26. The application that resulted in issuance of the ’259 patent was filed on  
17 July 31, 2003. The ’259 patent claims priority to July 31, 2003.

18 27. The ’259 patent generally relates to “methods for patterning dummy metal  
19 to achieve planarity for chemical-mechanical polishing of integrated circuits, and more  
20 particularly to a dummy fill software tool that provides clock-net aware dummy metal  
21 using dummy regions.” Ex. A at 1:7–11.

22 28. The background section of the ’259 patent identifies the shortcomings of  
23 the prior art. More specifically, the specification describes that the prior circuit design  
24 methodology was disadvantageous because it was “often impossible to insert enough  
25 dummy metal into a tile to meet the required minimum density without reducing the  
26 large dummy-to-clock distance.” Ex. A at 2:3–10. Use of this design process meant that  
27 a second run of the metal-fill tool was often required in order to meet the density  
28

1 requirements for all of the tiles. Ex. A at 2:10–14. Having to rerun the tool to meet the  
2 density requirements made the design process an “involved, iterative process[,]” which  
3 could “significantly impact the design schedule.” Ex. A at 2:14–18.

4 29. In light of the drawbacks of the prior art, the ’259 Inventors recognized  
5 the need to “minimize[] the negative timing impact of dummy metal on clock nets,  
6 while at the same time achieving minimum density in a single run.” Ex. A at 2:19–23.  
7 The inventions claimed in the ’259 patent addresses this need.

8 30. The ’259 patent contains three independent claims and 37 total claims,  
9 covering a method and computer readable medium for circuit design. Claim 1 reads:

10 1. A method for inserting dummy metal into a circuit design, the  
11 circuit design including a plurality of objects and clock nets, the  
12 method comprising:

13 (a) identifying free spaces on each layer of the circuit design  
14 suitable for dummy metal insertion as dummy regions, and

15 (b) prioritizing the dummy regions such that the dummy  
16 regions located adjacent to clock nets are filled with dummy  
17 metal last, thereby minimizing any timing impact on the clock  
18 nets.

19 31. This claim, as a whole, provides significant as a whole, provides  
20 significant benefits and improvements to the function of the semiconductor device, *e.g.*,  
21 minimizing the negative timing impact of dummy metal on clock nets while also  
22 reducing the opportunity for dishing and erosion that could result in inaccurate transfer  
23 of patterns during lithography, suboptimal layouts/designs, inaccurate timing, reduced  
24 signal integrity, crosstalk delay, noise issues increased probability of failure, and  
25 ultimately defective or underperforming devices. *See, e.g.*, Ex. A at 6:11–15.

26 32. The claims of the ’259 patent also recite inventive concepts that improve  
27 the functioning of the fabrication process, particularly as to dummy filling. The claims  
28 of the ’259 patent disclose a new and novel solution to specific problems related to

1 improving semiconductor fabrication. As explained in detail above and in the '259  
2 patent specification, the claimed inventions improve upon the prior art processes by  
3 prioritizing dummy regions such that the dummy regions located adjacent to clock nets  
4 are filled with dummy metal last. This has the advantage of reducing the impact of  
5 dummy metal on signal and clock lines and increasing the efficiency, yield, and  
6 design/layout miniaturization and flexibility of the manufacturing process. The claimed  
7 inventive processes also increase performance and signal integrity, while reducing  
8 crosstalk delay, noise issues, probability of failure, and defective and/or  
9 underperforming devices.

10 **U.S. PATENT NO. 6,436,807**

11 33. Bell Semic is the owner by assignment of the '807 patent. The '807 patent  
12 is titled "Method for Making an Interconnect Layer and a Semiconductor Device  
13 Including the Same." The '807 patent issued on August 20, 2002. A true and correct  
14 copy of the '807 patent is attached as Exhibit D.

15 34. The inventors of the '807 patent are Donald Cwynar, Sudhanshu Misra,  
16 Dennis Ouma, Vivek Saxena, and John Sharpe.

17 35. The application that resulted in the issuance of the '807 patent was filed  
18 on January 18, 2000. The '807 patent claims priority to January 18, 2000.

19 36. The '807 patent generally relates to "a method for making a layout for an  
20 interconnect layer that has uniform density throughout to facilitate planarization during  
21 manufacturing of a semiconductor device." Ex. D at 2:43–46. The background section  
22 of the '807 patent identifies the shortcomings of the prior art. More specifically, the  
23 specification describes that the prior circuit design methodology was disadvantageous  
24 because it could lead to "protrusions[] in the upper surface of the dielectric material[]  
25 above respective active interconnect features[.]" *Id.* at 1:40–42. The specification states  
26 that "if pattern density variations of the active interconnect features[] are large, CMP is  
27 not adequate to sufficiently planarize the interconnect layer[.]" *Id.* at 1:67–2:2.

1 Although “[c]onventional layout algorithms” were typically used to place dummy fill  
2 features in open areas of the interconnect layer, those algorithms placed dummy metal  
3 “based upon a predetermined set density.” *Id.* at 2:17–21. Relying on “predetermined  
4 set densit[ies]” could lead to the unnecessary placement of dummy fill features, which  
5 in turn could increase the parasitic capacitance of the interconnect layer. *Id.* at 2:31–33.  
6 The specification notes that “variations in the density of the interconnect layer [could]  
7 cause deviations when the interconnect layer [was] planarized.” *Id.* at 2:35–37.

8 37. In light of the drawbacks of the prior art, the ’807 Inventors recognized “a  
9 need for making a layout for an interconnect layer that determines placement of dummy  
10 fill features for achieving a uniform density throughout the interconnect layer.” Ex. D  
11 at 2:37–40. The inventions claimed in the ’807 patent address this need.

12 38. The ’807 patent contains two independent claims and 18 total claims.  
13 Claim 1 reads:

14 1. A method for making a layout for an interconnect layer of a  
15 semiconductor device to facilitate uniformity of planarization  
16 during manufacture of the semiconductor device, the method  
17 comprising the steps of:

18 (a) determining an active interconnect feature density for each  
19 of a plurality of layout regions of the interconnect layout; and

20 (b) adding dummy fill features to each layout region to obtain  
21 a desired density of active interconnect features and dummy  
22 fill features to facilitate uniformity of planarization during  
23 manufacturing of the semiconductor device, the adding  
24 comprising defining a minimum dummy fill feature lateral  
dimension based upon a dielectric layer deposition bias for a  
dielectric layer to be deposited over the interconnect layer.

25 39. This claim, as a whole, provides significant benefits and improvements to  
26 the function of the semiconductor device, *e.g.*, uniform planarization during  
27  
28

1 manufacturing, avoidance of adding unnecessary dummy fill features, and minimizing  
2 parasitic capacitance. *See, e.g.*, Ex. D at 5:9–34.

3 40. The claims of the '807 patent also recite inventive concepts that improve  
4 the functioning of the fabrication process, particularly as to dummy filling. The claims  
5 of the '807 patent disclose a new and novel solution to specific problems related to  
6 improving semiconductor fabrication. As explained in detail above and in the '807  
7 patent specification, the claimed inventions improve upon the prior art processes by  
8 determining an active interconnect feature density for each of a plurality of layout  
9 regions of the interconnect layout and adding dummy fill to each layout region to obtain  
10 a desired density of active interconnect features and dummy fill features to facilitate  
11 uniformity of planarization. This has advantages such as avoiding the unnecessary  
12 adding of dummy fill features and minimizing the parasitic capacitance of the  
13 interconnect layer.

14 **COUNT I – INFRINGEMENT OF U.S. PATENT NO. 7,007,259**

15 41. Bell Semic re-alleges and incorporates by reference the allegations of the  
16 foregoing paragraphs as if fully set forth herein.

17 42. The '259 patent is valid and enforceable under the United States Patent  
18 Laws.

19 43. Bell Semic owns, by assignment, all right, title, and interest in and to the  
20 '259 patent, including the right to collect for past damages.

21 44. A copy of the '259 patent is attached at Exhibit A.

22 45. On information and belief, NXP has and continues to directly infringe  
23 pursuant to 35 U.S.C. § 271(a) one or more claims of the '259 patent by using the  
24 patented methodology to design one or more semiconductor devices, including as one  
25 example the NXP Accused Product, in the United States.

26 46. On information and belief, NXP employs a variety of design tools, for  
27 example, Cadence, Synopsys, and/or Siemens tools, to insert dummy metal into a  
28

1 circuit design (the “’259 Accused Processes”) as recited in the ’259 patent claims. As  
2 one example, NXP’s Accused Processes perform a method for inserting dummy metal  
3 into a circuit design, where the circuit design includes a plurality of objects and clock  
4 nets\_as required by claim 1 of the ’259 patent. NXP does so by employing a design tool,  
5 such as at least one of a Cadence, Synopsys, and/or Siemens tool, to insert dummy  
6 metal into a circuit design for the NXP Accused Product. The NXP Accused Product’s  
7 design includes a plurality of objects, such as cells, interconnects, signal nets, and clock  
8 nets.

9 47. NXP’s ’259 Accused Processes also identify free spaces on each layer of  
10 the circuit design suitable for dummy metal insertion as dummy regions. NXP does so  
11 by employing a design tool, such as at least one of the Cadence, Synopsys, and/or  
12 Siemens tools, to identify free spaces on each layer of the NXP Accused Product’s  
13 circuit designs suitable for dummy metal insertion as dummy regions.

14 48. NXP’s ’259 Accused Processes also prioritize the dummy regions such  
15 that the dummy regions located adjacent to clock nets are filled with dummy metal last,  
16 thereby minimizing any timing impact on the clock nets. NXP does so by employing a  
17 design tool, such as at least one of the Cadence, Synopsys, and/or Siemens tools, to  
18 prioritize dummy regions such that those adjacent to clock nets are filled with dummy  
19 metal last. For example, the ’259 Accused Processes assign a “high cost” to adding  
20 metal fill near the clock nets and “lower cost” to adding metal fill near signal, power,  
21 and ground nets. Assigning “cost” in this way fills dummy regions adjacent to clock  
22 nets last and minimizes any timing impact on the clock nets.

23 49. An exemplary infringement analysis showing infringement of one or more  
24 claims of the ’259 patent is set forth in Exhibit B. The declaration of Lloyd Linder, an  
25 expert in the field of semiconductor device design, is attached at Exhibit C and further  
26 describes NXP’s infringement of the ’259 patent.

27  
28

1           50. NXP’s ’259 Accused Processes infringe and continue to infringe one or  
2 more claims of the ’259 patent during the pendency of the ’259 patent.

3           51. On information and belief, NXP has and continues to infringe directly  
4 pursuant to 35 U.S.C. § 271, *et. seq.*, either literally or under the doctrine of equivalents,  
5 by using the ’259 Accused Processes in violation of one or more claims of the ’259  
6 patent. NXP has and continues to infringe directly pursuant to 35 U.S.C. § 271, *et. seq.*,  
7 either literally or under the doctrine of equivalents, by making, selling, or offering to  
8 sell in the United States, or importing into the United States products manufactured or  
9 otherwise produced using the ’259 Accused Processes in violation of one or more  
10 claims of the ’259 patent.

11           52. NXP’s infringement of the ’259 patent is exceptional and entitles Bell  
12 Semic to attorneys’ fees and costs incurred in prosecuting this action under 35 U.S.C.  
13 § 285.

14           53. Bell Semic has been damaged by NXP’s infringement of the ’259 patent  
15 and will continue to be damaged unless NXP is enjoined by this Court. Bell Semic has  
16 suffered and continues to suffer irreparable injury for which there is no adequate  
17 remedy at law. The balance of hardships favors Bell Semic, and public interest is not  
18 disserved by an injunction.

19           54. Bell Semic is entitled to recover from NXP all damages that Bell Semic  
20 has sustained as a result of NXP’s infringement of the ’259 patent, including without  
21 limitation and/or not less than a reasonable royalty.

22           **COUNT II – INFRINGEMENT OF U.S. PATENT NO. 6,436,807**

23           55. Bell Semic re-alleges and incorporates by reference the allegations of the  
24 foregoing paragraphs as if fully set forth herein.

25           56. The ’807 patent is valid and enforceable under the United States Patent  
26 Laws.



1 57. Bell Semic owns, by assignment, all right, title, and interest in and to the  
2 '807 patent, including the right to collect for past damages.

3 58. A copy of the '807 patent is attached at Exhibit D.

4 59. On information and belief, NXP has and continues to directly infringe  
5 pursuant to 35 U.S.C. § 271(a) one or more claims of the '807 patent by using the  
6 patented methodology to design one or more semiconductor devices, including as one  
7 example the NXP Accused Product, in the United States.

8 60. On information and belief, NXP employs a variety of design tools, for  
9 example, Cadence, Synopsys, and/or Siemens tools, to make a layout for an  
10 interconnect layer of a semiconductor device (the "'807 Accused Processes") as recited  
11 in the '807 patent claims. As one example, NXP's '807 Accused Processes perform a  
12 method for making a layout for an interconnect layer of a semiconductor device, where  
13 the layout facilitates uniformity of planarization during manufacture of the  
14 semiconductor device as required by claim 1 of the '807 patent. NXP does so by  
15 employing a design tool, such as at least one of a Cadence, Synopsys, and/or Siemens  
16 tool, to make a layout for the interconnect layer of its NXP Accused Product. The NXP  
17 Accused Product layout facilitates uniformity of planarization during manufacture of  
18 the device.

19 61. NXP's '807 Accused Processes also determine an active interconnect feature  
20 density for each of a plurality of layout regions of the interconnect layout. NXP does  
21 so by employing a design tool, such as at least one of the Cadence, Synopsys, and/or  
22 Siemens tools, to determine an active interconnect feature density for each of a plurality  
23 of layout regions of the interconnect layout of its Accused Product.

24 62. NXP's '807 Accused Processes also add dummy fill features to each layout  
25 region to obtain a desired density of active interconnect features and dummy fill  
26 features to facilitate uniformity of planarization during manufacturing of the  
27 semiconductor device, the adding comprising defining a minimum dummy fill feature  
28

1 lateral dimension based upon a dielectric layer deposition bias for a dielectric layer to  
2 be deposited over the interconnect layer.

3 63. NXP does so by employing a design tool, such as at least one of the Cadence,  
4 Synopsys, and/or Siemens tools, to add dummy fill features to each layout region to  
5 obtain a desired density of active interconnect features and dummy fill features to  
6 facilitate uniformity of planarization during manufacturing of the semiconductor  
7 device. The adding of dummy fill through the use of these design tools comprises  
8 defining a minimum dummy fill feature lateral dimension based upon a dielectric layer  
9 deposition bias for a dielectric layer to be deposited over the interconnect layer. An  
10 exemplary infringement analysis showing infringement of one or more claims of the  
11 '807 patent is set forth in Exhibit E. The declaration of Lloyd Linder, an expert in the  
12 field of semiconductor device design, is attached at Exhibit C and further describes  
13 NXP's infringement of the '807 patent.

14 64. NXP's '807 Accused Processes infringe and continue to infringe one or  
15 more claims of the '807 patent during the pendency of the '807 patent.

16 65. On information and belief, NXP has and continues to infringe directly  
17 pursuant to 35 U.S.C. § 271, *et. seq.*, either literally or under the doctrine of equivalents,  
18 by using the '807 Accused Processes in violation of one or more claims of the '807  
19 patent. NXP has and continues to infringe directly pursuant to 35 U.S.C. § 271, *et. seq.*,  
20 either literally or under the doctrine of equivalents, by making, selling, or offering to  
21 sell in the United States, or importing into the United States products manufactured or  
22 otherwise produced using the '807 Accused Processes in violation of one or more  
23 claims of the '807 patent.

24 66. NXP's infringement of the '807 patent is exceptional and entitles Bell Semic  
25 to attorneys' fees and costs incurred in prosecuting this action under 35 U.S.C. § 285.

67. Bell Semic is entitled to recover from NXP all damages that Bell Semic has sustained as a result of NXP’s infringement of the ’807 patent, including without limitation and/or not less than a reasonable royalty.

**PRAYER FOR RELIEF**

WHEREFORE, Bell Semic respectfully requests that this Court enter judgment in its favor as follows and award Bell Semic the following relief:

- (a) a judgment declaring that NXP has infringed one or more claims of the ’259 and ’807 patents in this litigation pursuant to 35 U.S.C. § 271, *et seq.*;
- (b) an award of damages adequate to compensate Bell Semic for infringement of the ’259 and ’807 patents by NXP, in an amount to be proven at trial, including supplemental post-verdict damages until such time as NXP ceases its infringing conduct;
- (c) a permanent injunction, pursuant to 35 U.S.C. § 283, prohibiting NXP and its officers, directors, employees, agents, consultants, contractors, suppliers, distributors, all affiliated entities, and all others acting in privity with NXP, from committing further acts of infringement with respect to the ’259 patent;
- (d) a judgment requiring NXP to make an accounting of damages resulting from NXP’s infringement of the ’259 and ’807 patents;
- (e) the costs of this action, as well as attorneys’ fees as provided by 35 U.S.C. § 285;
- (f) pre-judgment and post-judgment interest at the maximum amount permitted by law;
- (g) all other relief, in law or equity, to which Bell Semic is entitled.

1 Dated: January 31, 2023

*/s/ Alan Block*

2 Alan Block (SBN 143783)  
3 ablock@mckoolsmith.com  
4 **MCKOOL SMITH, P.C.**  
5 300 South Grand Avenue, Suite 2900  
6 Los Angeles, California 90071  
7 Telephone: (213) 694-1200  
8 Facsimile: (213) 694-1234

9 James R. Patterson, SBN 211102  
10 jim@pattersonlawgroup.com  
11 Jennifer M. French, SBN 265422  
12 jenn@pattersonlawgroup.com  
13 **PATTERSON LAW GROUP, APC**  
14 1350 Columbia Street, Unit 603  
15 San Diego, California 92101  
16 Telephone: (619) 756-6990  
17 Facsimile: (619) 756-6991

18 Christopher R. Clayton\* (MO SBN 69692)  
19 **DEVLIN LAW FIRM LLC**  
20 1526 Gilpin Avenue  
21 Wilmington, Delaware 19806  
22 Telephone: (302) 449-9010  
23 Facsimile: (302) 353-4251  
24 \* *Admitted pro hac vice*

25 *Attorneys for Plaintiff Bell Semiconductor, LLC*

1 **DEMAND FOR JURY TRIAL**

2 Plaintiff hereby demands a jury trial for all issues so triable.

3 Dated: January 31, 2023

/s/ Alan Block

4 Alan Block (SBN 143783)  
5 ablock@mckoolsmith.com  
6 **MCKOOL SMITH, P.C.**  
7 300 South Grand Avenue, Suite 2900  
8 Los Angeles, California 90071  
9 Telephone: (213) 694-1200  
10 Facsimile: (213) 694-1234

11 James R. Patterson, SBN 211102  
12 jim@pattersonlawgroup.com  
13 Jennifer M. French, SBN 265422  
14 jenn@pattersonlawgroup.com  
15 **PATTERSON LAW GROUP, APC**  
16 1350 Columbia Street, Unit 603  
17 San Diego, California 92101  
18 Telephone: (619) 756-6990  
19 Facsimile: (619) 756-6991

20 Christopher R. Clayton\* (MO SBN 69692)  
21 **DEVLIN LAW FIRM LLC**  
22 1526 Gilpin Avenue  
23 Wilmington, Delaware 19806  
24 Telephone: (302) 449-9010  
25 Facsimile: (302) 353-4251  
26 \* *Admitted pro hac vice*

27 *Attorneys for Plaintiff Bell Semiconductor, LLC*